

Title (en)  
Exposure method

Title (de)  
Belichtungsverfahren

Title (fr)  
Procédé d'exposition

Publication  
**EP 0997781 A1 20000503 (EN)**

Application  
**EP 99308452 A 19991026**

Priority  
JP 32143298 A 19981027

Abstract (en)  
An exposure method for exposing a workpiece in a proximity exposure system, includes a first exposure step for printing, by exposure, an image of a first mask pattern on a predetermined portion of the workpiece, and a second exposure step for printing, by exposure, an image of a second mask pattern, different from the first mask pattern, on the predetermined portion of the workpiece, wherein exposures in the first and second exposure steps are performed superposedly, prior to a development process. <IMAGE>

IPC 1-7  
**G03F 7/20**; **G03F 1/14**

IPC 8 full level  
**B81C 1/00** (2006.01); **G03F 1/00** (2012.01); **G03F 1/14** (2006.01); **G03F 7/20** (2006.01); **H01L 21/027** (2006.01); **G03F 7/00** (2006.01)

CPC (source: EP KR US)  
**G03F 1/70** (2013.01 - EP US); **G03F 7/2022** (2013.01 - EP US); **G03F 7/7035** (2013.01 - EP US); **G03F 7/70466** (2013.01 - EP US); **H01L 21/027** (2013.01 - KR); **G03F 7/001** (2013.01 - EP US)

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